

# A temperature independent emission component in the capacitance transients of deep-level defects in germanium

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## Introduction

Treatments involving high temperatures, e.g. quenching, may introduce impurities and point defects in Ge, which may give rise to deep levels in the band gap and which may reduce the carrier lifetimes.

An adequate technique to study these defects is Deep Level Transient Spectroscopy (DLTS). In one of the DLTS signals of quenched p-type Ge an additional emission component has been observed when using large time windows. The characteristics of this emission have been compared to those of the recently studied Co<sup>+0</sup> level in Co-implanted p-type Ge [1] which also exhibits such behaviour.

## Additional emission component

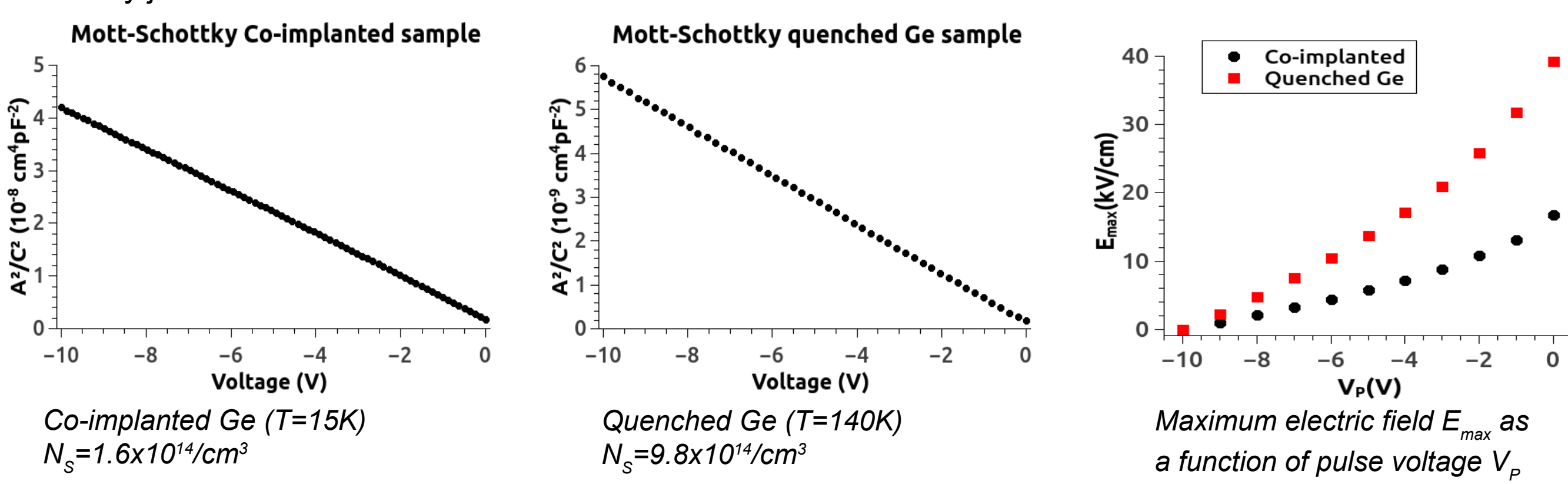
### Experimental

p-type germanium samples (10x10x2mm<sup>3</sup>).

"Co-implanted": (5.10<sup>13</sup> cm<sup>-2</sup>) at 90 keV + Thermal Annealing at 500°C (5 min).

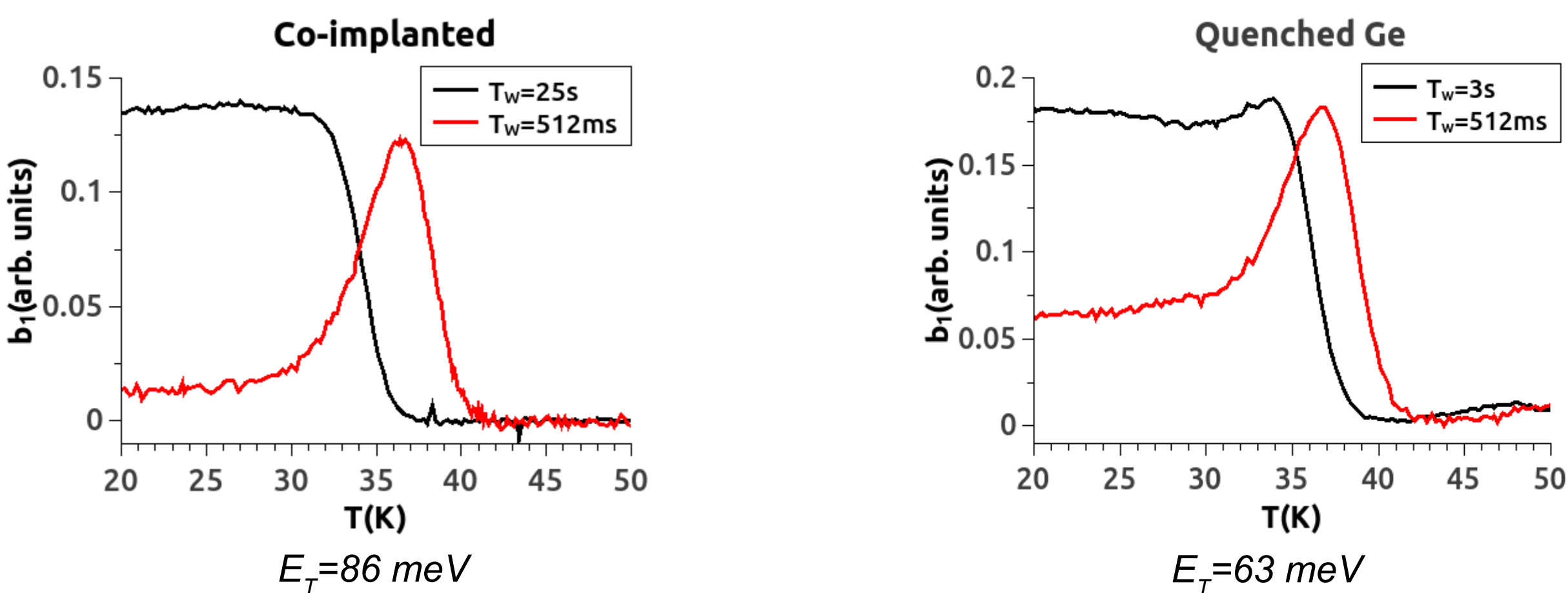
"Quenched Ge": 30 min in preheated tube furnace (700°C) + quenched in silicon oil (25°C)

The samples were etched (HF+HNO<sub>3</sub>) and prepared for DLTS measurements by evaporating In to form Schottky junctions.



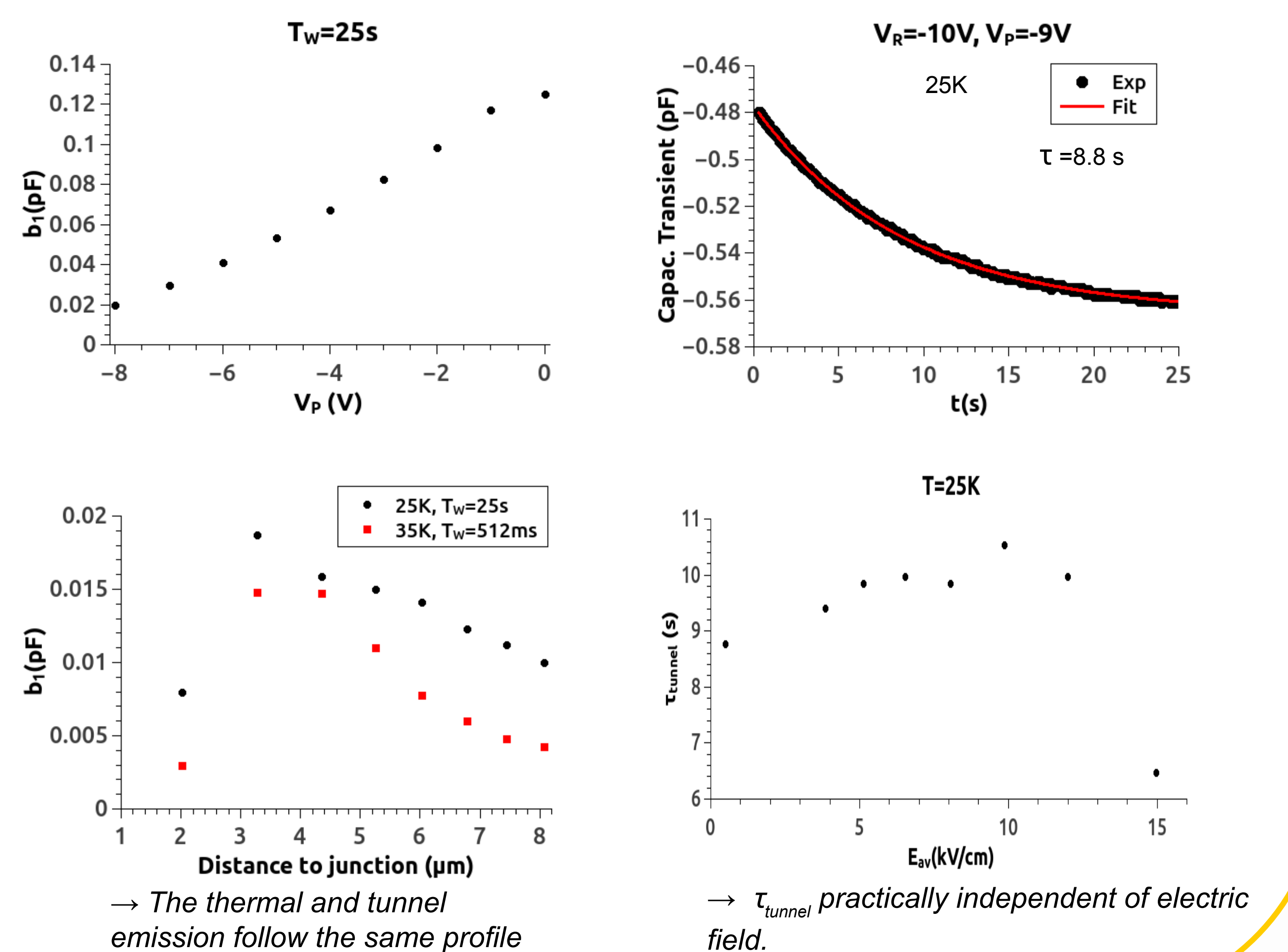
Ohmic contacts were prepared using In-Ga eutectic and In foil. Capacitance transients were measured after a pulse from  $V_R$  (-10V) to  $V_P$ . The DLTS time window is denoted by  $T_w$ . A pulse duration of 100 ms was used for  $T_w < 1$  s and 200 ms for  $T_w > 1$  s.

### Observation

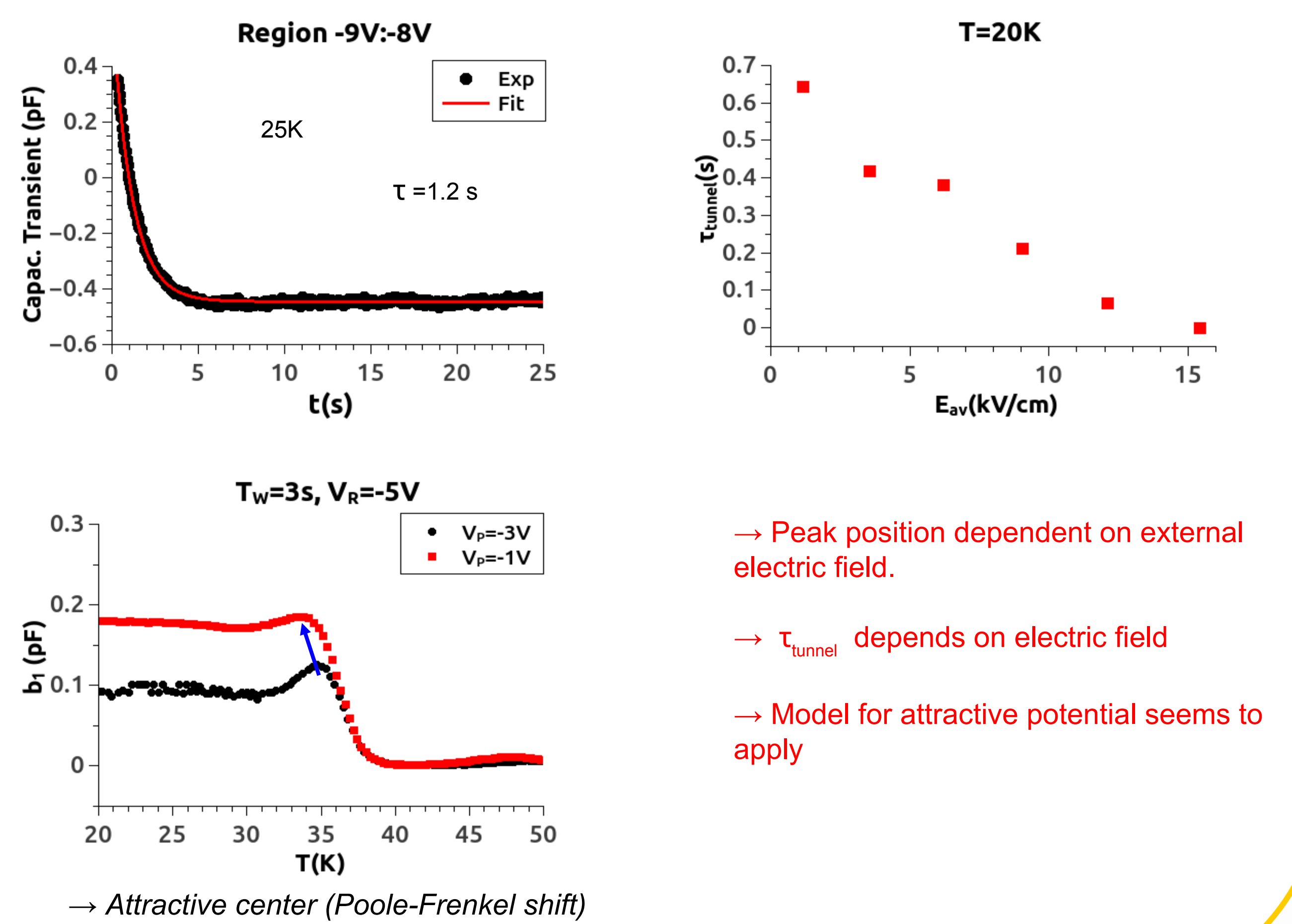


→ "Tunneling"-plateau is "shunted" as soon as the thermionic effect begins [2]

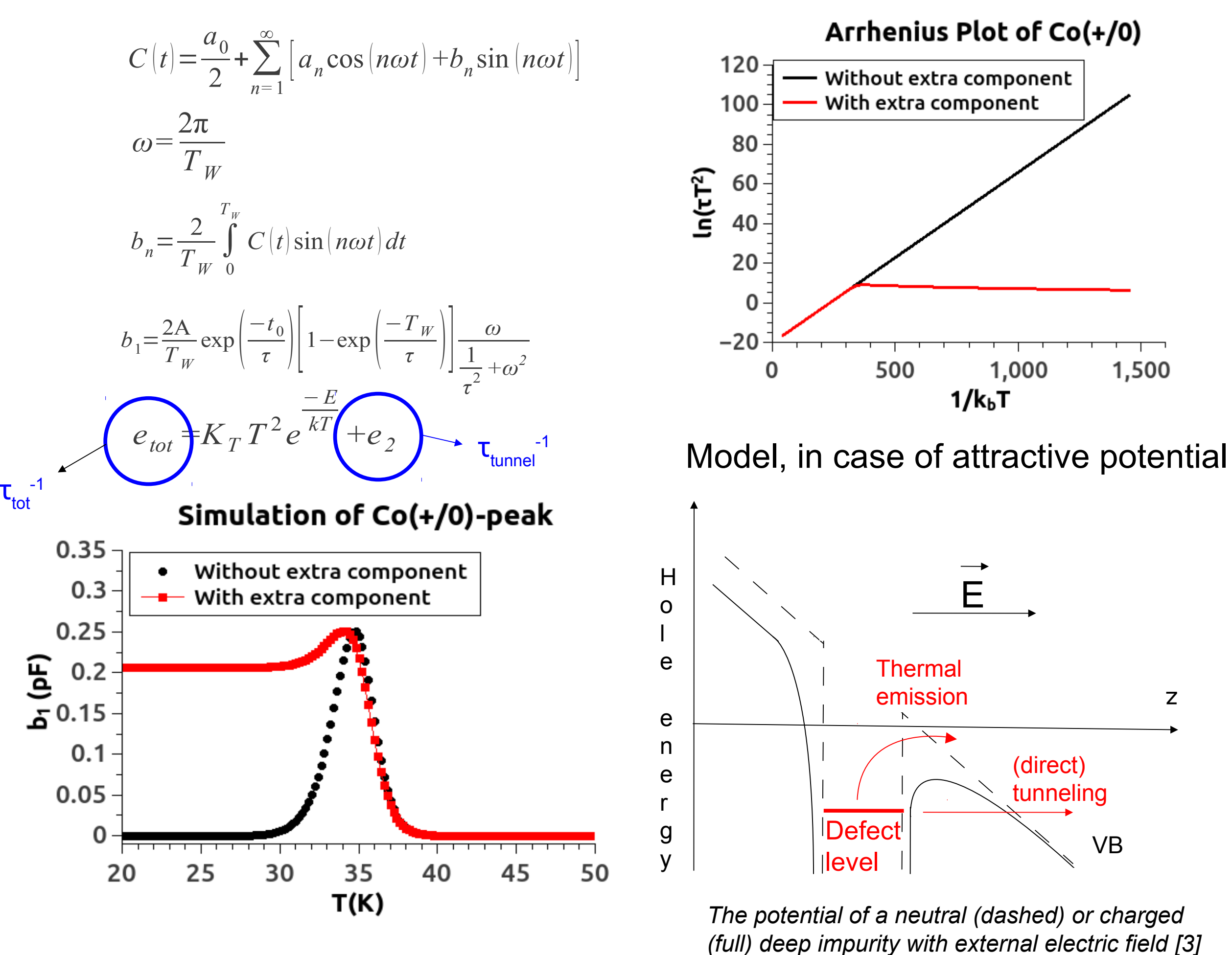
## Co-implanted Ge



## Quenched Ge



## Simulation



## Conclusions

	Charge	PF-shift	E-dep. $\tau$
Co-implanted	0	X	X
Quenched Ge	-	V	V

→ The two investigated deep defects in Ge exhibit two parallel emission paths, one from thermal emission and a second one attributed to localized level-to-band tunneling.  
 → For the "neutral" hole trap level Co<sup>+0</sup>, the tunnel time was observed to be practically independent of electric field.  
 → The quenching induced level ( $E_T = 63$  meV) is attractive to holes (Poole-Frenkel effect) and here the tunnel time appears to be electric field dependent.

## References

- [1] J. Lauwaert, J. Vanhellefont, E. Simoen, H. Vrielinck and P. Clauws, J. APPL. PHYS, submitted (2012)
- [2] X. Letartre, D. Stiévenard and M. Lannoo, J. APPL. PHYS **69** (10) 7336-7338 (1991)
- [3] S.D. Ganichev, I.N. Yassievich and W. Prettl, J. PHYS.: CONDENS. MATTER **14** R1263-1295 (2002)

